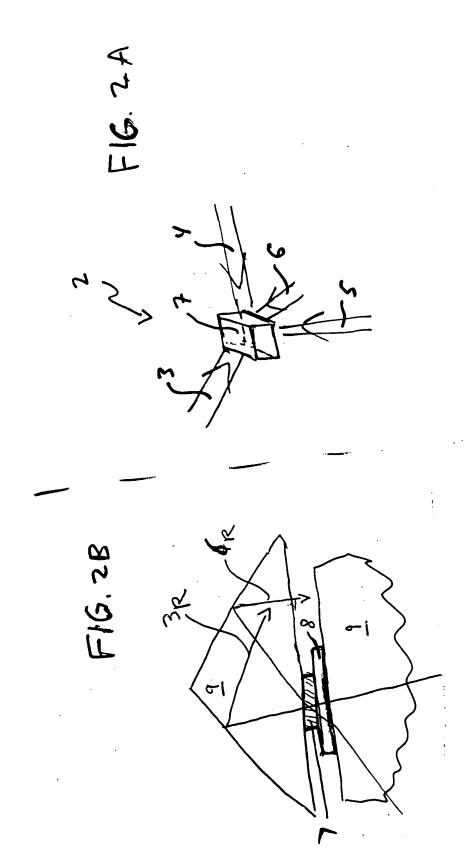
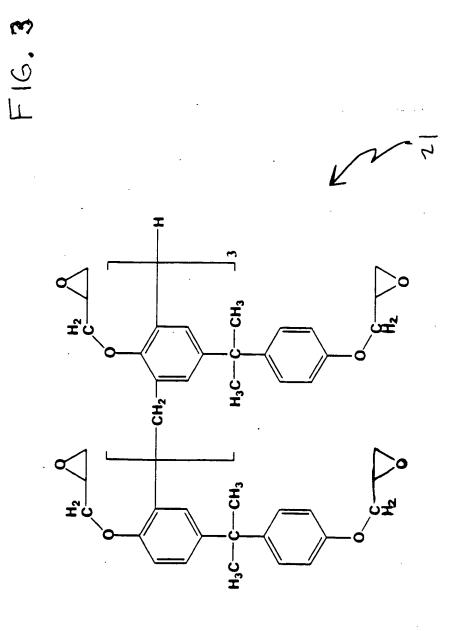
Provide photo-sensitive medium
Liz
Expose +)
Expose the medium to an intensity pattern under conditions that inhibit refractive index changes
-14
Heat the exposed medium to favorize refractive index changing meti
refractive index changing reactions
reactions
16
(1)0.01 (1)
either reacted or une to remove
either reacted or unreacted portions of the medium
L10
/8
Dry the washed medium
Dry the washed medium under conditions that limit internal stresses
CZO
1
\mathcal{N}^{\cdot}
10
F16. 1





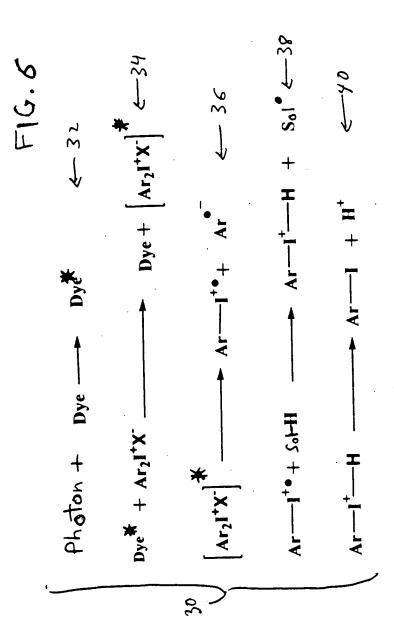
F16.4A

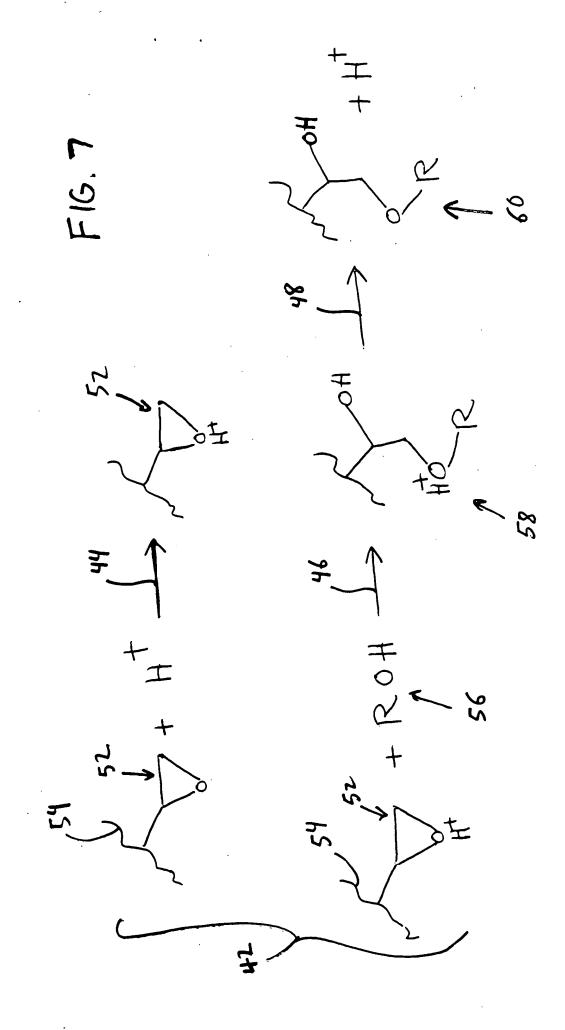
F16.48

F16.4C

F16.5A

F16.5B





Provide Photo-sensitive medium
C12
Expose the medium to an intensity-pattern
under conditions that inhibit retractive index changes
-14
Segnentially expose a selected set of points and/or lines with a focal
of points and/or lines with a tocal
region of a converging light beam
72
Heat the exposed medium to
favorize polymerization of oligoners therein
L ₁₆
Wash the cured medium to remove
unpolymerized oligoners
C18
V V
Dry the washed medium under conditions that limit internal stresses
27
70 F16. 9
10 L

Form a 3D polymer crystalline templ	ate
- C82	
Fill holes in the template with a higher retractive index filler material	gh
C84	
Burn or etch away the polymer of stalline template from the block	:ry-
~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~	
80° F16°	7

